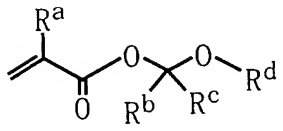
ABSTRACT

A polymeric compound having a repeated unit corresponding to an unsaturated carboxylic acid hemiacetal ester represented by the following formula (1);



(1)

wherein R^a is a hydrogen atom, a halogen atom, an alkyl group of carbon number 1 to 6 or a haloalkyl group of carbon number 1 to 6, R^b is a hydrocarbon group having a hydrogen atom at a first poison, R^c is a hydrogen atom or a hydrocarbon group and R^d is an organic group having a cyclic skeleton. This polymeric compound, further, may have a repeated unit corresponding to at least one monomer selected from a monomer having a lactone skeleton, a monomer having a cyclic ketone skeleton, a monomer having an acid anhydride group and a monomer having an imide group [except for a repeated unit corresponding to the said unsaturated carboxylic acid hemiacetal ester] and/or a repeated unit corresponding to at least one monomer selected from a monomer having a hydroxyl group and others. This polymeric compound shows superior acid-eliminating function in case of using as photoresist.